

DAFTAR PUSTAKA

- Alonso, M. dan Finn, E.J., 1980, *Fundamental University Physics*, 2nd edition, Addison-Wesley Publishing Company Inc., 76-79.
- Beiser, A., 1992, *Konsep Fisika Modern*, edisi ketiga, Erlangga, Jakarta, 54-57.
- Carlson, W.G. dan Gupta, T.K., 1982, "Transparent conducting ZnO:Al films deposited by r.f. magnetron-sputtering", *J. Appl. Physics*, **53**, 5746-5749.
- Chopra, K.L., 1996, "XPS and X-ray diffraction studies of aluminum-doped zinc oxide transparent conducting films", *Thin Solid Films*, **280**, 20-25.
- Cullity, B.D., 1978, *Elements of X-Ray Diffraction*, Second edition, Addison-Wesley Publishing Company Inc., Philippines.
- Eckertova, L., 1986, *Physics of Thin Films*, Second revised edition, Plenum Publishing Corporation, New York, 96-99, 121-126.
- Gordon, R.G., 2000, "Criteria for choosing transparent conductors", *Mrs. Bulletin August*, 52-57.
- Instruction Manual UV-Vis 1601PC Spectrophotometer*, 1993, Shimadzu, Japan.
- Joint Committee on Powder Diffraction Standards*, Powder Diffraction File 36-1451, JCPDS, Swarthmore.
- Kittel, C., 1976, *Introduction to Solid State Physics*, 5th edition, John Wiley and Sons, New York.
- Konuma, M., 1991, *Film Deposition by Plasma Techniques*, Internal edition, Springer-Verlag Berlin Heidelberg, New York.
- Korb, L.J., 1983, *Metals Handbook*, Ninth Edition, Volume 13 Corrosion, ASM International, Metals Park, Ohio.
- Matsuda, A., 1988, "Amorphous silicon from glow discharge plasma", edited by Parangtopo, Muliawati, G.S., *Proceedings International Workshop on Physics of Materials*, Jakarta, 250-255.
- Mrowec, S., 1980, *Defects and Diffusion in Solids an Introduction*, Elsevier Scientific Publishing Company, New York, 43-95.

- Minami, T., 1982, "Highly conductive and transparent zinc oxide films prepared by r.f. magnetron sputtering under an applied external magnetic field", *Appl. Phys. Lett.*, **41**(10).
- Ohring, M., 1992, *The Materials Science of Thin Films*, International edition, Academic Press Inc., Boston, 103-120, 265-267, 514.
- Puchert, M.K., 1996, "Postdeposition annealing of radio frequency magnetron sputtered ZnO films", *J. Applied Physics*, **14**(4).
- Reitz, J.R., 1979, *Foundations of Electromagnetic Theory*, 3rd edition, Addison-Wesley Publishing Company Inc., New York, 471-501.
- Runyan, W.R., 1975, *Semiconductor Measurements and Instrumentation*, International student edition, MCGraw-Hill Kogakusha LTD, Tokyo, Japan, 153-168.
- Sanchez, J.A., 1998, "Electrical and optical properties of aluminum-doped ZnO thin films prepared by spray pyrolysis", *Thin Solid Films*, **333**, 196-202.
- Schaffler, R. dan Schock, H.W., 1998, "Electron microscopic characterization of reactively sputtering ZnO films with different Al-doping levels", *Thin Solid Films*, **330**, 108-113.
- Smits, F.M., 1958, "Measurement of resistivity with the four-point probe", *Bell System Technical Journal*, **37**, 371-374.
- Stuart, V.R., 1983, *Vacuum Technology, Thin Film and Sputtering*, Academic Press Inc., Tokyo, Japan.
- Szyszkka, B., 1999, "Transparent and conductive aluminium doped zinc oxide films prepared by mid-frequency reactive magnetron sputtering", *Thin Solid Films*, **351**, 164-169.
- Tominaga, K., 1998, "Transparent conductive ZnO films preparation by alternating sputtering of ZnO:Al and Zn or Al targets", *Thin Solid Films*, **334**, 35-39.
- Takahashi, K. dan Konagai, M., 1986, *Amorphous Silicon Solar Cells*, North Oxford Academic Publishers Ltd, Tokyo, Japan.
- Takai, O., 1998, "Nanostructure of ZnO thin films prepared by reactive rf magnetron sputtering", *Thin Solid Films*, **318**, 117-119.
- Taylor, J.R., 1982, *An Introduction to Error Analysis : The Study of Uncertainties in Physical Measurements*, University Science Books, USA, 56-67.

Van De Pol, F.C.M., 1990, "Thin films ZnO-properties and application", *J. Ceramic Bulletin*, Vol. 69(12), 741-745.

Wasa, K. dan Hayakawa, S., 1992, *Handbook of Sputter Deposition Technology, Principles, Technology and Applications*, Noyes Publications, Osaka, Japan, 19-99, 124-146.

Wilson, W.W., 1994, *Study of Transparent Conducting ZnO Grown by Metalorganic Chemical Vapor Deposition and Its Applications to Amorphous Silicon Solar Cells*, Doctoral Dissertation, Tokyo Institute of Technology, Japan, 5-10.

Yamada, A. dan Konagai, M., 1993, "Application of transparent conducting ZnO films to a-Si solar cells", *J. Appl. Phys.*, Vol. 32(9), 3764-3769.